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**AVR Studio 419 With AVR Toolchain 419iso ~UPD~**



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1. Field of the Invention The present invention relates to a method of binding a primer and a photosensitive composition used in the same, and more specifically, to a method of binding a primer which involves adding functional groups to either or both of the primer and the photosensitive composition and a photosensitive composition used in the same.

2. Discussion of the Background In the fabrication of a liquid crystal display device or an organic light-emitting display device, a process of patterning a photo-hardened photoresist is carried out on a transparent conductive film provided as a supporting member, thereby forming a transparent electrode (photo-hardening conductive film) for each of the transparent electrodes (pixel electrodes) for forming each of pixels. During the formation of the transparent electrode, for the purpose of improving the efficiency of the patterning process and reducing the cost of a device, a so-called "one-side coating type" in which a primer for improving the adhesion between the transparent conductive film and the photo-hardened photoresist is coated on one side of the transparent conductive film and then the photo-hardened photoresist is coated thereon has been widely used. In a method of forming a photo-hardened photoresist pattern described in, for example, Japanese Patent Application Laid-Open (JP-A) No. 2008-239535, a primer is coated by a spin coating method and then a photo-hardened photoresist is coated by a spin coating method, thereby forming the photo-hardened photoresist. Subsequently, the photo-hardened photoresist is baked, and then the photo-hardened photoresist is exposed and developed. Thereafter, the photo-hardened photoresist and the primer exposed by the development are subjected to a reflow treatment, thereby removing a primer and the photo-hardened photoresist which have not been subjected to the reflow treatment from each other. In addition, in the methods



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